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**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q67844

Takako SUZUKI, et al.

Appln. No.: 10/084,204

Group Art Unit: 1752

Confirmation No.: 6177

Examiner: John S. Y. Chu

Filed: February 28, 2002

For: POSITIVE PHOTORESIST COMPOSITION AND PROCESS FOR FORMING RESIST  
PATTERN USING SAME

**RESPONSE UNDER 37 C.F.R. § 1.111**

**MAIL STOP AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated November 17, 2005, please consider the remarks as submitted herewith on the accompanying pages.

Claims 17-20 are all the claims pending in the application. Claims 17-20 have been rejected under 35 U.S.C. § 112, first and second paragraphs. Claims 17-20 have also been rejected under 35 U.S.C. § 103.

**Response to the Rejection of Claims 17-20 under 35 U.S.C. § 112, first and second paragraphs**

Claims 17-20 were rejected under 35 U.S.C. 112, first paragraph, as allegedly failing to comply with the enablement requirement.

It is the Examiner's position that the quinonediazide methyl gallate compound (b2) is critical to the practice of the invention, but not included in the claim(s). Specifically, the